

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Original): Aqueous solution for post-etch residue removal having a reduced etching rate, comprising an organic acid from the group consisting of hydroxy-carboxylic acids and/or the group consisting of mono-, di- and tricarboxylic acids, in the presence of an oxidant, and optionally additives for improving the cleaning action and inertisation to Al, Cu, Ti, W, Al/Cu, TiN and SiO₂ surfaces.

Claim 2 (Original): Aqueous solution according to Claim 1, comprising corrosion inhibitors selected from the group consisting of imidazoline compounds.

Claim 3 (Currently Amended): Aqueous solution according to ~~Claims 1 and 2~~Claim 1, comprising one or more compounds from the group consisting of benzimidazoles, aminobenzimidazoles and 2-alkylbenzimidazoles, ~~including alkyl-substituted imidazolines and 1,2-dialkylimidazolines and oleic hydroxyethyl imidazoline~~ as corrosion inhibitors.

Claim 4 (Original): Aqueous solution according to Claim 1, comprising at least one aprotic polar solvent.

Claim 5 (Currently Amended): Aqueous solution according to ~~Claims 1 and 4~~Claim 1, comprising at least one aprotic polar solvent from the group consisting of N-methylpyrrolidone (NMP), ethylene glycol, propylene glycol, dimethyl sulfoxide (DMSO) and 1-methoxy-2-propyl acetate (PGMEA).

Claim 6 (Original): Aqueous solution according to Claim 1, comprising at least one surface-active substance.

Claim 7 (Currently Amended): Aqueous solution according to ~~Claims 1 and 6~~Claim 1, comprising at least one anionic surfactant and/or nonionic surfactant as surface-active substance.

Claim 8 (Original): Aqueous solution according to Claim 7, comprising at least one anionic surfactant from the group consisting of aliphatic carboxylic acids and alkylbenzenesulfonic acids and/or at least one nonionic surfactant from the group consisting of alkyl oxalkylates and alkylphenol oxethylates.

Claim 9 (Original): Aqueous solution according to Claim 8, comprising at least one anionic surfactant from the group consisting of heptanoic acid, octanoic acid and dodecylbenzenesulfonic acid and/or at least one nonionic surfactant from the group consisting of fatty alcohol alkoxylates, octylphenol oxethylates and polyoxyethylene sorbitan fatty acid esters (Tween[®]).

Claim 10 (Currently Amended): Aqueous solution according to ~~Claims 1 to 9~~Claim 1, comprising at least one organic acid from the group consisting of glycolic acid, lactic acid, hydroxybutyric acid, glyceric acid, malic acid, tartaric acid, citric acid, malonic acid, succinic acid, glutaric acid and maleic acid.

Claim 11 (Currently Amended): Aqueous solution according to ~~Claims 1 to 9~~Claim 1, comprising at least one oxidant from the group consisting of hydrogen peroxide and ammonium peroxodisulfate.

Claim 12 (Currently Amended): Aqueous solution according to ~~Claims 1 to 11~~Claim 1, comprising an organic acid from the group consisting of hydroxycarboxylic acids and/or the group consisting of mono-, di- and tricarboxylic acids in an amount of from 0.1 to 30%, based on the total weight.

Claim 13 (Currently Amended): Aqueous solution according to ~~Claims 1 to 11~~Claim 1, comprising an oxidant in an amount of from 0.1 to 10%, based on the total weight.

Claim 14 (Currently Amended): Aqueous solution according to ~~Claims 1 to 11~~Claim 1, comprising at least one corrosion inhibitor in an amount of from 1 ppm to 1%, based on the total weight.

Claim 15 (Currently Amended): Aqueous solution according to ~~Claims 1 to 11~~Claim 1, comprising at least one aprotic polar solvent in an amount of from 0.1 to 10%, based on the total weight.

Claim 16 (Currently Amended): Aqueous solution according to ~~Claims 1 to 11~~Claim 1, comprising at least one aprotic polar solvent in an amount of from 0.1 to 10%, based on the total weight.

Claim 17 (Currently Amended): Aqueous solution according to ~~Claims 1 to 11~~Claim 1, comprising at least one anionic surfactant in an amount of from 1 ppm to 1%, based on the weight, and/or at least one nonionic surfactant in an amount of from 1 ppm to 1%, based on the weight.

Claim 18 (Currently Amended): Aqueous solution according to ~~Claims 1 to 11~~Claim 1, comprising at least one wetting agent from the group consisting of enanthic acid, Triton[®] X100, Tween[®] 20, dodecylbenzenesulfonic acid and Plurafac[®] 120 in an amount of from 100 to 1000 ppm.

Claim 19 (Currently Amended): Aqueous solution according to ~~Claims 1 to 11~~Claim 1, comprising citric acid, hydrogen peroxide, N-methylpyrrolidone (NMP) and optionally additives.

Claim 20 (Original): Solution according to Claim 19, comprising citric acid in an amount of from 0.1 to 30%, hydrogen peroxide in an amount of from 0.1 to 10% and N-methylpyrrolidone in an amount of from 0.1 to 10%.

Claim 21 (Currently Amended): Solution according to ~~Claims 19—20~~Claim 19, comprising a corrosion inhibitor in an amount of from 1 ppm to 1% and a wetting agent in an amount of from 1 ppm to 1%.

Claim 22 (Currently Amended): ~~Use of~~The method of using an aqueous solution according to ~~Claims 1—21~~Claim 1 for the production of semiconductors on spray tools or in tank units.